

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	9823	selective\$3 near5 (clean\$6 or ((defect\$6 or impurity or thrust\$6 or spit\$6 or pit or swell\$6 or protrude\$6) near5 (remove\$6 or etch\$6)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/02 06:54
L2	3920	1 and (semiconductor GaSb or InAs or Si or silicon or InP or GaAs or InAs or AlSb)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/02 06:55
L3	2494	2 and (resist or photoreist or mask\$6 or sacrificial or protect\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/02 06:56
L4	2364	3 and (@ad<"20040225" or @rlad<"20040225")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/02 06:57